Author Index of Volume 250

Alidjanov, E. K., 268
Amm, D. T., 135
André, J.-J., 219
Ashrit, P. V., 47
Atabaev, B. G., 268
Austin, E., 20

Bader, G., 47
Badilescu, S., 47
Barlingay, C. K., 67
Basa, D. K., 187
Baud, G., 142
Bauer, P., 232
Besse, J. P., 142
Bialas, H., 42
Biederman, R. R., 1
Bodnar, I. V., 33
Boltaev, N. N., 268
Borisenko, V. E., 53
Brückl, H., 56

Chandran, B., 151
Chin, V. W. L., 263
Clyne, T. W., 172
Cruz, C. M. G., 273
Cserhati, A. F., 20

Davidson, K., 249
Dey, S. K., 67
Dietrich, D. A., 181
Ding, X., 126
Duchatelard, Ph., 142
de With, G., 115
dos Santos, M. P., 26

Ealet, B., 92
Eisele, I., 258
El-Faiky, H. E., 87
Elyakhoulfi, M. H., 92
Ericson, F., 157

Flietner, B., 258
Friedbacher, G., 72
Fromm, E., 61
Fujii, S., 8

Gaipov, S., 268
Gasser, W., 213
Gill, S. C., 172
Gillet, E., 92
Girouard, F. E., 47
Goforth, R. C., 151
Grasserbauer, M., 72
Gremenok, V. F., 33
Greve, D. W., 20
Grilhé, J., 37
Grozdanov, I., 67

Hallin, C., 157
Hatalis, M. K., 20
Hatta, A., 81
Haysom, J. E., 135
Hefny, M. M., 87
Hjort, K., 157
Hoffmann, H., 56
Hunter, R. A., 249
Hwang, D. K., 16

Ijichi, H., 164
Ishiguro, T., 243
Ivakin, G. I., 238
Ivanenko, L. I., 53

Jacquet, M., 142
Janzén, E., 157
Johnson, D. J., 135
Jones, R., 249
Junqua, N., 37

Kang, T. W., 202
Kastner, A., 101
Kim, D. Y., 202
Kim, T. W., 202
Kjindyak, A. S., 33
Kindyak, V. V., 33
Kitada, M., 111
Klechkovskaya, V. V., 238
Knoll, E., 42
Kobune, M., 8
Krushevski, E. A., 53
Küppers, J., 101

Laursen, T., 135
Lecheler, R., 56
Leskelä, M., 72
Lessard, R. A., 194
Li, X., 263
Li, X. P., 132
Lin, F., 20
Lin, W., 126
Lotz, B., 219

Maden, W., 61
Markl, J., 232
Martin, M., 61
Matsumura, M., 213
Medvedkin, G. A., 33
Meng, L.-J., 26
Mineshige, A., 8
Minh-Ha, N., 47
Mogoda, A. S., 87
Murakami, M., 164

Najdoski, M., 67
Nasrazadani, S., 151
Niinistö, L., 72
Nogami, Y., 243

Ohtani, T., 81
Oliveira, L., 273
Otsuki, A., 164
Ousi-Benomar, W., 194
Oyanagi, H., 243

Petit, M. A., 219
Prohaska, T., 72

Ramdani, S., 206
Reiss, G., 56
Ricci, M., 92
Ristov, M., 67
Ritala, M., 72
Rother, B., 181
Rud, Yu. V., 33
Ruzyllo, J., 16

Saemann-Ischenko, G., 232
Sahli, S., 206
Salih, S. A., 87
Sarcona, G., 20
Schindler, W., 232
Schweitz, J.-Å., 157
Segui, Y., 206
Severin, J. W., 115
Shibata, H., 81
Silva, M. A. P., 273
Sisson, Jr., R. D., 1
Siu Li, M., 273
Sohn, Y. H., 1
Strüber, U., 101
Sugie, Y., 8
Sukhorukov, G. A., 238

Tadanaga, O., 164
Takeuchi, S., 243
Takkouk, Z., 206
Tansley, T. L., 263
Tontsch, P., 232
Tressler, R. E., 16
Truong, V.-V., 47

Uchida, Y., 231
Ulrich, R. K., 151

Vancea, J., 56
van Haßelt, P., 232
van Weert, A. A. M., 115

Wachtel, H., 219
Wadayama, T., 81
Wang, Y. H., 132
Wittmann, J. C., 219

Xue, Q., 126
Xue, S., 194

Yang, D., 126

Zhang, X., 126

Subject Index of Volume 250

Adhesion
  alumina coatings on PMMA: optimization of adherence, 142
  evaluation of coating–substrate interface strength by differential load feed analysis of load-indentation measurements, 181
  influence of substrate chemistry on the adhesion of electrolessly deposited Ni(P) on metal oxide coated ceramics, 115
Adsorption
  growth and properties of thin Ag films on Pt(100) surfaces, 101
Alkali halides
  optical and structural characterizations of Cu^+-doped KCl films, 273
  target current spectroscopy of the alkali halides KCl, CsCl and KBr, 268
Aluminium
  oxidation of iron, aluminum and titanium films in the temperature range 50–200 °C, 61
Aluminium nitride
  dielectric properties of AlN films prepared by laser-induced chemical vapour desposition, 263
Aluminium oxide
  electronic and crystallographic structure of γ-alumina thin films, 92
  growth modes of epitaxial copper films on c-sapphire, 42
Amorphous materials
  correlation of structure and optical properties of an annealed hydrogenated amorphous silicon–carbon alloy film, 187
Atomic force microscopy
  development of crystallinity and morphology in hafnium dioxide thin films grown by atomic layer epitaxy, 72
Atomic layer epitaxy
  development of crystallinity and morphology in hafnium dioxide thin films grown by atomic layer epitaxy, 72

Boron
  evaluation of new high temperature boron solid planar diffusion sources through p–n junction characterization, 16
Boron nitride
  evaluation of new high temperature boron solid planar diffusion sources through p–n junction characterization, 16

Ceramics
  alumina coatings on PMMA: optimization of adherence, 142
  influence of substrate chemistry on the adhesion of electrolessly deposited Ni(P) on metal oxide coated ceramics, 115
Cerium oxide
  preparation and characteristics of Y_2O_3-doped CeO_2 films by r.f. magnetron sputtering, 8
Chemical vapour deposition
  quasi-monolayer deposition of silicon dioxide, 213
  real-time IR and mass spectroscopic study of the reaction process of WF_6 and a-S:H:F, 81
Chromium
  combined reaction and diffusion controlled kinetics of silicidation, 53
Coatings
  alumina coatings on PMMA: optimization of adherence, 142
  evaluation of coating–substrate interface strength by differential load feed analysis of load-indentation measurements, 181
  investigation of residual stress generation during thermal spraying by continuous curvature measurement, 172
  microstructural development in physical vapor-deposited partially stabilized zirconia thermal barrier coatings, 1
  phase structure characteristics of r.f. reactively sputtered zirconia thin film, 132
  study of lithium intercalation into tungsten oxide films prepared by different methods, 47
  yttrium oxide film deposition by a Langmuir–Blodgett processing technique and its incorporation into oxide scales by substrate oxidation, 135
Cobalt
  characterization of cobalt annealed on silicon–germanium epilayers, 20
Copper
  experimental study of the copper thiosulfate system with respect to thin-film deposition, 67
  growth modes of epitaxial copper films on c-sapphire, 42
  optical and structural characterizations of Cu^+-doped KCl films, 273
Copper oxide
  preparation and characteristics of Y_2O_3-doped CeO_2 films by r.f. magnetron sputtering, 8
Corrosion
  electrochemical behaviour of surface zirconium oxides in the presence of electroactive species, 87
Crystallization
  fabrication of thin crystal films of organic compounds, 238

Deposition process
  quasi-monolayer deposition of silicon dioxide, 213
  study of lithium intercalation into tungsten oxide films prepared by different methods, 47
Dielectric properties
  dielectric properties of AlN films prepared by laser-induced chemical vapour desposition, 263
Diffusion
  combined reaction and diffusion controlled kinetics of silicidation, 53
  evaluation of new high temperature boron solid planar diffusion sources through p–n junction characterization, 16
  reactions in Au/Nb bilayer thin films, 111

Elastic properties
  comparison of three techniques for measuring strain at fracture of thin film materials, 151
  investigation of residual stress generation during thermal spraying by continuous curvature measurement, 172
  thermal strain in indium thin films deposited on GaAs substrates, 164
Electrical properties and measurements
  dielectric properties of AlN films prepared by laser-induced chemical vapour desposition, 263
  ordered Langmuir–Blodgett films of a substituted lutetium bisphthalocyanine, 249
Electrochemistry
  electrochemical behaviour of surface zirconium oxides in the presence of electroactive species, 87

Electron energy loss spectroscopy
electronic and crystallographic structure of γ-alumina thin films, 92
Electron microscopy
anisotropic spin transport in oriented lithium phthalocyanine thin films, 219
Electron spin resonance
anisotropic spin transport in oriented lithium phthalocyanine thin films, 219
Epitaxy
growth modes of epitaxial copper films on c-sapphire, 42
hardness, internal stress and fracture toughness of epitaxial $Al_xGa_{1-x}As$ films, 157
surface strains and measurements of misfit dislocation density by diffraction methods in thin films on substrates, 37
Evaporation
optical properties of laser-evaporated $CuGaSe_2$ films near and above the fundamental absorption edge, 33
target current spectroscopy of the alkali halides KCl, CsCl and KBr, 268

Fourier transform infrared spectroscopy
r.f. plasma deposition from hexamethyldisiloxane–oxygen mixtures, 206

Gallium arsenide
hardness, internal stress and fracture toughness of epitaxial $Al_xGa_{1-x}As$ films, 157
optical properties of a strained GaAs/Si heterostructure after rapid thermal annealing, 202
thermal strain in indium thin films deposited on GaAs substrates, 164
Germanium
characterization of cobalt annealed on silicon–germanium epilayers, 20
Glow discharge
correlation of structure and optical properties of an annealed hydrogenated amorphous silicon–carbon alloy film, 187
Gold
reactions in Au/Nb bilayer thin films, 111

Hafnium oxide
development of crystallinity and morphology in hafnium dioxide thin films grown by atomic layer epitaxy, 72
Hardness
evaluation of coating–substrate interface strength by differential load feed analysis of load-indentation measurements, 181
hardness, internal stress and fracture toughness of epitaxial $Al_xGa_{1-x}As$ films, 157
Heterostructures
optical properties of a strained GaAs/Si heterostructure after rapid thermal annealing, 202
High energy electron diffraction
fabrication of thin crystal films of organic compounds, 238
surface strains and measurements of misfit dislocation density by diffraction methods in thin films on substrates, 37

Impurities
optical and structural characterizations of Cu^+-doped KCl films, 273
Indium
thermal strain in indium thin films deposited on GaAs substrates, 164
Infrared spectroscopy
real-time IR and mass spectroscopic study of the reaction process of WF_6 and a-S:H:F, 81
study of lithium intercalation into tungsten oxide films prepared by different methods, 47
Interfaces
evaluation of coating–substrate interface strength by differential load feed analysis of load-indentation measurements, 181
Ion implantation
surface physical and chemical changes of pure iron after molybdenum ion implantation and their effects on the tribological behaviour. II: Tribological behaviour, 126
Iron
α-Fe_2O_3 thin films prepared by metalorganic deposition (MOD) from Fe(III) 2-ethylhexanoate, 194
oxidation of iron, aluminum and titanium films in the temperature range 50–200 °C, 61
surface physical and chemical changes of pure iron after molybdenum ion implantation and their effects on the tribological behaviour. II: Tribological behaviour, 126
Iron oxide
α-Fe_2O_3 thin films prepared by metalorganic deposition (MOD) from Fe(III) 2-ethylhexanoate, 194

Langmuir–Blodgett films
fabrication of thin crystal films of organic compounds, 238
local structure of metal ions in arachidate Langmuir–Blodgett film, 243
ordered Langmuir–Blodgett films of a substituted lutetium bisphthalocyanine, 249
yttrium oxide film deposition by a Langmuir–Blodgett processing technique and its incorporation into oxide scales by substrate oxidation, 135
Luminescence
optical properties of a strained GaAs/Si heterostructure after rapid thermal annealing, 202

Magnetic properties and measurements
anisotropic spin transport in oriented lithium phthalocyanine thin films, 219
Metals
growth and properties of thin Ag films on Pt(100) surfaces, 101
influence of substrate chemistry on the adhesion of electrolessly deposited Ni(P) on metal oxide coated ceramics, 115
Molecular beam epitaxy
molecular beam epitaxial growth of $SmBa_2Cu_3O_{7-\delta}$ thin films and effect of substrate temperature on the surface roughness, 232
Molybdenum
surface physical and chemical changes of pure iron after molybdenum ion implantation and their effects on the tribological behaviour. II: Tribological behaviour, 126
Multilayers
growth and properties of thin Ag films on Pt(100) surfaces, 101
growth and structure of polycrystalline Cr/Au multilayered thin films, 56
reactions in Au/Nb bilayer thin films, 111

Nanostructures
quasi-monolayer deposition of silicon dioxide, 213
Niobium
reactions in Au/Nb bilayer thin films, 111
Nitrides
dielectric properties of AlN films prepared by laser-induced chemical vapour desposition, 263

Optical properties
α-Fe_2O_3 thin films prepared by metalorganic deposition (MOD) from Fe(III) 2-ethylhexanoate, 194
correlation of structure and optical properties of an annealed hydrogenated amorphous silicon–carbon alloy film, 187
direct current reactive magnetron sputtered zinc oxide thin films—the effect of the sputtering pressure, 26
experimental study of the copper thiosulfate system with respect to thin-film deposition, 67
optical and structural characterizations of Cu^+-doped KCl films, 273
optical properties of laser-evaporated $CuGaSe_2$ films near and above the fundamental absorption edge, 33
ordered Langmuir–Blodgett films of a substituted lutetium bisphthalocyanine, 249
Organic substances
anisotropic spin transport in oriented lithium phthalocyanine thin films, 219
local structure of metal ions in arachidate Langmuir–Blodgett film, 243
Oxidation
oxidation of iron, aluminum and titanium films in the temperature range 50–200 °C, 61
yttrium oxide film deposition by a Langmuir–Blodgett processing technique and its incorporation into oxide scales by substrate oxidation, 135
Oxides
electrochemical behaviour of surface zirconium oxides in the presence of electroactive species, 87
influence of substrate chemistry on the adhesion of electrolessly deposited Ni(P) on metal oxide coated ceramics, 115
Oxygen ion conductor
preparation and characteristics of Y_2O_3-doped CeO_2 films by r.f. magnetron sputtering, 8

Phthalocyanine
ordered Langmuir–Blodgett films of a substituted lutetium bisphthalocyanine, 249
Physical vapour deposition
microstructural development in physical vapor-deposited partially stabilized zirconia thermal barrier coatings, 1
phase structure characteristics of r.f. reactively sputtered zirconia thin film, 132
preparation and characteristics of Y_2O_3-doped CeO_2 films by r.f. magnetron sputtering, 8
Plasma processing and deposition
investigation of residual stress generation during thermal spraying by continuous curvature measurement, 172
r.f. plasma deposition from hexamethyldisiloxane–oxygen mixtures, 206
Platinum
work function measurements for gas detection using tin oxide layers with a thickness between 1 and 200 nm, 258
Polymers
alumina coatings on PMMA: optimization of adherence, 142

Radiation damage
target current spectroscopy of the alkali halides KCl, CsCl and KBr, 268
Reaction kinetics
combined reaction and diffusion controlled kinetics of silicidation, 53
Rutherford backscattering spectroscopy
yttrium oxide film deposition by a Langmuir–Blodgett processing technique and its incorporation into oxide scales by substrate oxidation, 135

Scanning tunnelling microscopy
growth and structure of polycrystalline Cr/Au multilayered thin films, 56
Secondary electron emission
target current spectroscopy of the alkali halides KCl, CsCl and KBr, 268
Semiconductors
correlation of structure and optical properties of an annealed hydrogenated amorphous silicon–carbon alloy film, 187
experimental study of the copper thiosulfate system with respect to thin-film deposition, 67
optical properties of laser-evaporated $CuGaSe_2$ films near and above the fundamental absorption edge, 33
Sensors
work function measurements for gas detection using tin oxide layers with a thickness between 1 and 200 nm, 258
Silicides
characterization of cobalt annealed on silicon–germanium epilayers, 20
combined reaction and diffusion controlled kinetics of silicidation, 53
Silicon
optical properties of a strained GaAs/Si heterostructure after rapid thermal annealing, 202
real-time IR and mass spectroscopic study of the reaction process of WF_6 and a-S:H:F, 81
Silicon oxide
quasi-monolayer deposition of silicon dioxide, 213
r.f. plasma deposition from hexamethyldisiloxane–oxygen mixtures, 206
Solar cells
optical properties of laser-evaporated $CuGaSe_2$ films near and above the fundamental absorption edge, 33
Sputtering
direct current reactive magnetron sputtered zinc oxide thin films—the effect of the sputtering pressure, 26
phase structure characteristics of r.f. reactively sputtered zirconia thin film, 132
Stress
hardness, internal stress and fracture toughness of epitaxial $Al_xGa_{1-x}As$ films, 157
investigation of residual stress generation during thermal spraying by continuous curvature measurement, 172
Structural properties
characterization of cobalt annealed on silicon–germanium epilayers, 20
development of crystallinity and morphology in hafnium dioxide thin films grown by atomic layer epitaxy, 72
direct current reactive magnetron sputtered zinc oxide thin films—the effect of the sputtering pressure, 26
growth and structure of polycrystalline Cr/Au multilayered thin films, 56
local structure of metal ions in arachidate Langmuir–Blodgett film, 243

Sulphides
experimental study of the copper thiosulfate system with respect to thin-film deposition, 67
Superconductivity
molecular beam epitaxial growth of $SmBa_2Cu_3O_{7-\delta}$ thin films and effect of substrate temperature on the surface roughness, 232
Surface morphology
growth and properties of thin Ag films on Pt(100) surfaces, 101
molecular beam epitaxial growth of $SmBa_2Cu_3O_{7-\delta}$ thin films and effect of substrate temperature on the surface roughness, 232
Surface roughness
molecular beam epitaxial growth of $SmBa_2Cu_3O_{7-\delta}$ thin films and effect of substrate temperature on the surface roughness, 232
Surface stress
surface strains and measurements of misfit dislocation density by diffraction methods in thin films on substrates, 37
Surface structure
electronic and crystallographic structure of γ-alumina thin films, 92
surface strains and measurements of misfit dislocation density by diffraction methods in thin films on substrates, 37

Tin oxide
work function measurements for gas detection using tin oxide layers with a thickness between 1 and 200 nm, 258
Titanium
oxidation of iron, aluminum and titanium films in the temperature range 50–200 °C, 61
Titanium nitride
evaluation of coating–substrate interface strength by differential load feed analysis of load-indentation measurements, 181
Transmission electron microscopy
fabrication of thin crystal films of organic compounds, 238
growth and structure of polycrystalline Cr/Au multilayered thin films, 56
Tribology
surface physical and chemical changes of pure iron after molybdenum ion implantation and their effects on the tribological behaviour. II: Tribological behaviour, 126
Tungsten
real-time IR and mass spectroscopic study of the reaction process of WF_6 and a-S:H:F, 81
Tungsten oxide
study of lithium intercalation into tungsten oxide films prepared by different methods, 47

Work function
work function measurements for gas detection using tin oxide layers with a thickness between 1 and 200 nm, 258

X-ray absorption
local structure of metal ions in arachidate Langmuir–Blodgett film, 243
X-ray diffraction
growth modes of epitaxial copper films on c-sapphire, 42
phase structure characteristics of r.f. reactively sputtered zirconia thin film, 132
thermal strain in indium thin films deposited on GaAs substrates, 164
X-ray photoelectron spectroscopy
electronic and crystallographic structure of γ-alumina thin films, 92
r.f. plasma deposition from hexamethyldisiloxane–oxygen mixtures, 206

Zinc oxide
direct current reactive magnetron sputtered zinc oxide thin films—the effect of the sputtering pressure, 26
Zirconium
electrochemical behaviour of surface zirconium oxides in the presence of electroactive species, 87
microstructural development in physical vapor-deposited partially stabilized zirconia thermal barrier coatings, 1